

The electrochemical characteristics of amorphous  $V_2O_5$  thin film cathodes prepared by sputtering method

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Recently, Thin film rechargeable batteries have received significant attention due to their broad applications such as micro-sensors, smart cards, and micro-electro-mechanical system (MEMS) devices. The energy storage capacity is in general dependent on cathode materials. It is well-known that the transition metal oxides, such as  $LiCoO_2$ ,  $LiMn_2O_4$ ,  $LiNiO_2$  have been extensively studied due to their high voltages close to 4 V and long cycle life. However, these materials have certain drawback because the deposition temperatures are relatively high (about 400~800 °C), which seems to be a restriction on practical applications. It is reported that vanadium oxide film is considered to be a promising candidate because it can be deposited at lower temperature. Moreover, vanadium oxide film have demonstrated high specific capacity and fairly good rechargeability in the voltage window between 3.5 V and 1.5 V.

Vanadium oxide film were prepared on Pt/Ti/Si substrate by rf magnetron sputtering using a  $V_2O_5$  target in a mixed Ar+O<sub>2</sub> atmosphere. Pt and Ti are cathode current collector and adhesion layer, respectively. Substrate temperature fixed on 200 °C.  $V_2O_5$  target fabricated  $V_2O_5$  powder (Junsei Chemical Co. Ltd) and PVA(poly vinyl alcohol) by solid state sintering. The target to substrate distance was 6 cm. The rf power and total pressure were 60 W and 15 mTorr. Ar-O<sub>2</sub> gas mixture ratio was 70/30.

The film thickness measured y a Tencor Alpha-step profiler.

X-ray diffraction data (XRD) were obtained using M18XHF-SRA in the  $2\theta$  range from 15 to 35° with Cu K $\alpha$  radiation ( $\lambda = 1.5406 \text{ \AA}$ ). Electrochemical characterization of the prepared film was performed in liquid electrolyte. Active area of sputtered vanadium oxide thin film for electrochemical analysis was about 1 cm<sup>2</sup>. 1M LiClO<sub>4</sub> in PC (propylene carbonate) and a Li foil were used as a liquid electrolyte and an anode, respectively.

The galvanostatic charge/discharge test was carried out with WBCS 3000 charge/discharge analyzer at constant current density 100  $\mu A/cm^2$  in the voltage window between 4 V and 1.5 V.

Our as-deposited  $V_2O_5$  thin film shows amorphous behavior and we achieve crystalline structure by heat treatment. Despite as-deposited  $V_2O_5$  thin film shows irreversible capacity loss at first cycling, it shows approximately double capacity contrast to crystalline one. But heat-treated  $V_2O_5$  thin film shows vivid voltage plateau at entire chare/discharge curves.

In conclusion, amorphous  $V_2O_5$  exhibit better electrochemical properties, compared to crystalline ones. Amorphous  $V_2O_5$  shows high capacity and small capacity fading compared with crystalline  $V_2O_5$ . However both two samples show excellent charge/discharge efficiency.